

Amendments to the Abstract:

Please replace the paragraph beginning at page 7, line 3, with the following rewritten paragraph:

5 ~~A cleaning mechanism for system having a combination of a substrate and a~~
 ~~frame layer being cleaned includes an image sensor package, the cleaning~~
 ~~mechanism a sealed up body is formed with a cleaning room. A rotating device is~~
 located within the cleaning room of the sealed up body. A cleaning device is
 located within the cleaning room of the sealed up body. A cleaning device is
 mounted on the a side of the cleaning room of the sealed up body, and ejects a
 ~~cleaner directly into the chamber in a direction opposite to a direction of a~~
10 ~~centrifugal force of the combination of the substrate and the frame layer is~~
 ~~cleaned a chamber of a substrate by cleaner. The rotating device is configured to~~
 ~~fix the combination of the substrate and the frame layer with the chamber facing~~
 ~~the cleaning device.~~